

AMENDED CLAIMS					
	NO. OF CLAIMS	HIGHEST NO. OF CLAIMS PREVIOUSLY PAID FOR	EXTRA CLAIMS	RATE	ADDT'L FEE
Total Claims	22	MINUS 21 =	1	x \$18.00 (103) =	18.00
Independent Claims	4	MINUS 3 =	1	x \$78.00 (102) =	78.00
If Amendment adds multiple dependent claims, add \$260.00 (104)					
Total Amendment Fee					96.00
If small entity status is claimed, subtract 50% of Total Amendment Fee					
<b>TOTAL ADDITIONAL FEE DUE FOR THIS AMENDMENT</b>					<b>96.00</b>

☐ A claim fee in the amount of \$\_\_\_\_\_ is enclosed.

☒ Charge \$ 96.00 to Deposit Account No. 02-4800.

The Commissioner is hereby authorized to charge any appropriate fees under 37 C.F.R. §§ 1.16, 1.17 and 1.21 that may be required by this paper, and to credit any overpayment, to Deposit Account No. 02-4800. This paper is submitted in duplicate.

Respectfully submitted,

BURNS, DOANE, SWECKER & MATHIS, L.L.P.

By:

Peter K. Skiff  
 Peter K. Skiff  
 Registration No. 31,917

P.O. Box 1404  
 Alexandria, Virginia 22313-1404  
 (703) 836-6620

Date: November 24, 1999

# 1768

Attorney's Docket No. 15290-238

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

Jeffrey HUNG et al.

Application No.: 09/002,007

Filed: December 31, 1997

For: ETCHING PROCESS FOR ORGANIC  
ANTI-REFLECTIVE COATING



Group Art Unit: 1765

Examiner: L. Vinh

AMENDMENT/REPLY TRANSMITTAL LETTER

Assistant Commissioner for Patents  
Washington, D.C. 20231

Sir:

Enclosed is a reply for the above-identified patent application.

☐ A Petition for Extension of Time is also enclosed.

☐ Also enclosed is \_\_\_\_\_

☐ \_\_\_\_\_ statement(s) claiming small entity status  
☐ are also enclosed ☐ were submitted previously.

☐ A Request for Entry and Consideration of Submission under 37 C.F.R. § 1.129(a)  
(146/246) is also enclosed.

☐ No additional claim fee is required.

☒ An additional claim fee is required, and is calculated as shown below:

RECEIVED  
NOV 30 1999  
TC 1700 MAIL ROOM

#10/B

Patent  
Attorney's Docket No. 015290-238

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Patent Application of

Jeffrey HUNG et al.

Application No.: 09/002,007

Filed: December 31, 1997

For: ETCHING PROCESS FOR ORGANIC  
ANTI-REFLECTIVE COATING



Group Art Unit: 1765

Examiner: L. Vinh

**AMENDMENT**

Assistant Commissioner for Patents  
Washington, D.C. 20231

Sir:

In response to the Official Action dated August 25, 1999, please amend the above-identified application as follows.

**IN THE CLAIMS:**

Please amend Claims 1, 6, 11 and 14 and add new Claim 22 as follows:

Claim 1, line 1, change "layer" to --layer,--.

Claim 6, line 3, change "photo etching" to --exposure--.

Claim 11, line 2, change "circuit" to --circuit,--.

RECEIVED  
NOV 30 1999  
1C-1700 MAIL ROOM

B1 14. (Twice Amended) The oxygen-free [plasma etching gas formulation] system of etching agents of Claim 1, [consisting] wherein the system of etching agents consists

11/26/1999 CVORACHA 00000078 024800 09002007

01 FC:103 18.00 CH  
02 FC:102 78.00 CH